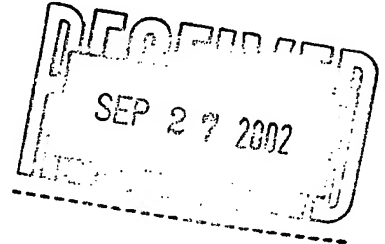




2881 #2
9-30-02

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Abdurrahman Sezginer et al. PATENT APPLICATION
Serial No.: 10/074,561 Group Art Unit: 2881
Filed: February 12, 2002 Examiner:
For: OVERLAY ALIGNMENT METROLOGY
USING DIFFRACTION GRATINGS



Information Disclosure Statement

Hon. Assistant Commissioner
for Patents
Washington, D.C. 20231

Sir:

The following information is submitted in compliance with Applicants' duty of disclosure under 37 CFR § 1.56. A copy of each reference is enclosed.

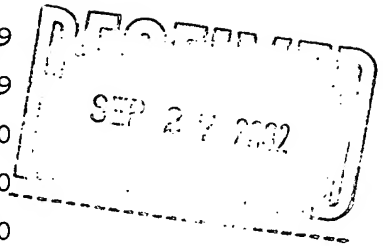
<u>Pat. No.</u>	<u>U.S. Patents</u> <u>Patentee</u>	<u>Grant Date</u>
4,103,998	Nakazawa et al.	08/01/78
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5,100,237	Wittekoek et al.	03/31/92
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5,867,276	McNeil et al.	02/02/99
5,889,593	Bareket	03/30/99
5,963,329	Conrad et al.	10/05/99
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Foreign Patent Documents

<u>Publ. No.</u>	<u>Country</u>	<u>Publ. Date</u>
WO 99/45340	PCT	Sept. 10, 1999

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N.T. Sullivan et al., "Semiconductor Pattern Overlay", Handbook of Critical Dimension Metrology and Process Control, Proceedings of conf. 28-29 Sept. 1993, Monterey, CA, K.M. Monahan, *SPIE Optical Engineering Press*, Vol. CR52, pp. 160-188.

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R.M. Silver et al., "Overlay Metrology: Recent Advances and Future Solutions", *Future Fab International*, Issue 11, London, July 2001, 17 pages.

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CERTIFICATE OF MAILING

I hereby certify that this paper (along with any paper referred to as being attached or enclosed) is being deposited with the United States Postal Service on the date shown below with sufficient postage as first class mail in an envelope addressed to: Asst. Commissioner for Patents, Washington, D.C. 20231

Signed: *Sally Azevedo*
Typed Name: Sally Azevedo

Date: August 28, 2002

Respectfully submitted,

Thomas Schneck

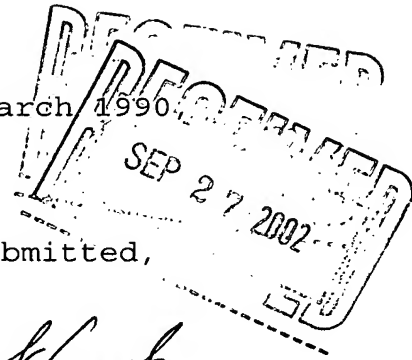
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FORM PTO-1449

SEP 03 2002

Atty. Docket No.
SEN-019Serial No.
10/074,561LIST OF PRIOR ART
CITED BY APPLICANTApplicant:
Abdurrahman Sezginer et al.Filing Date:
February 12, 2002Group:
2881

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Examiner Initial*	Document Number	Grant Date	Name	Class	Sub Class	Filing Date
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AB	4,172,664	10/30/79	Charsky et al.	356	356	
AC	4,200,395	04/29/80	Smith et al.	356	356	
AD	4,311,389	01/19/82	Fay et al.	356	354	
AE	4,332,473	06/01/82	Ono	356	356	
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AJ	5,608,526	03/04/97	Piwonka-Corle et al.	356	369	

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AL	N.T. Sullivan et al., "Semiconductor Pattern Overlay", Handbook of Critical Dimension Metrology and Process Control, Proceedings of Conf. 28-29 Sept. 1993, Monterey, CA, K.M. Monahan, SPIE Optical Engineering Press, Vol. CR52, pp. 160-188.
AM	Printout, Nikon KrF Step-and-Repeat Scanning System NSR-S205C, July 2000.
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AO	J. Opsal et al., "Broadband Spectral Operation of a Rotating-Compensator Ellipsometer", Thin Solid Films, 1998, Vol. 313-314, pp. 58-61.

EXAMINER:

DATE CONSIDERED:

*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

FORM PTO-1449					Atty. Docket No. SEN-019		Serial No. 10/034,561	
LIST OF PRIOR ART CITED BY APPLICANT				Applicant: Abdurrahman Sezginer et al.				
				Filing Date: February 12, 2002		Group: 2881		
U.S. PATENT DOCUMENTS								
Examiner Initial*	Document Number	Grant Date	Name		Class	Sub Class	Filing Date	
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BB	5,808,742	09/15/98	Everett et al.		356	363		
BC	5,867,276	02/02/99	McNeil et al.		356	445		
BD	5,889,593	03/30/99	Bareket		356	445		
BE	5,963,329	10/05/99	Conrad et al.		356	372		
BF	6,023,338	02/08/00	Bareket		356	401		
BG	6,079,256	06/27/00	Bareket		73	105		
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BJ	6,150,231	11/21/00	Muller et al.		438	401		
FOREIGN PATENT DOCUMENTS								
Examiner Initial*	Document Number	Grant Date	Country	Class	Sub Class	Translation Yes No		
BK								
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
BL	X. Niu et al., "Specular Spectroscopic Scatterometry in DUV Lithography", SPIE, March 1999, Vol. 3677, pp. 159-168. ,							
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BO								
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